

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S81	1501015	"<110>"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 13:04
S83	92	("<110>" and silicon and probe). clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 13:05
S82	21268	"<110>" and silicon and probe	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 13:05
S16 3	110	S162 and boron	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 13:07
S16 2	321	cantilever and tip and anisotropic\$4 and "110" and crystal\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 13:07
S16 1	77	((reactive adj ion adj etch\$.ti.) or ((dry adj etch\$4).ti.)) and ((helium or he) and ((sulfur adj hexaflu\$6) or ("SF.sub.6") or (sf6)) and (o2 or oxygen))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S16 0	0	((reactive adj ion adj etch\$.ti.) and he and sf6 and o2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S15 9	0	((reactive adj ion adj etch\$.ti.) and he and (o2 or "o.sub\$4") and (sulfur adj hexaflu\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S15 8	1518	(reactive adj ion adj etch\$.ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S15 7	51	((probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 216/2) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 148/33.3) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/306) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/719) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/750) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/754)) and "1,1,0"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S15 6	11	"5026437".URPN.	USPAT	OR	OFF	2006/04/11 13:07
S15 5	85	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 216/2) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 148/33.3) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/306) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/719) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/750) or (probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/754)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S15 4	21	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/754	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S15 3	2	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/750	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S15 2	3	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 324/719	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S15 1	40	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S15 0	40	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/307	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 9	59	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 250/306	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 8	1	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 148/33.3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 7	10	probe and cantilever and mask and silicon and (boron or boron-diffus\$4) and 216/2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 6	1955	73/105	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 5	4340	324/754	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S14 4	831	324/750	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 3	542	324/719	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 2	2746	250/307	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 1	3211	250/306	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S14 0	517	148/33.3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S13 9	2008	216/2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S13 8	0	216/11.216/2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S13 7	908	(((reactive adj ion) or (dry adj etch\$4)) and cantilever and layer) and "(110)"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S13 6	1860	((reactive adj ion) or (dry adj etch\$4))and cantilever and layer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S13 5	908	(((reactive adj ion) or (dry adj etch\$4)) and cantilever and layer) and "110"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S13 4	1860	((reactive adj ion) or (dry adj etch\$4)) and cantilever and layer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S13 3	22	(reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6")) and cantilever and layer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S13 2	43	"5021364".URPN.	USPAT	OR	OFF	2006/04/11 13:07
S13 1	39	"4968585".URPN.	USPAT	OR	OFF	2006/04/11 13:07
S13 0	787	tip and cantilever and (silicon adj dioxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 9	16	((cantilever and probe and tip) and "250"/\$.ccls.) and dop\$3 and ((dry adj etch\$4) or (reactive adj ion adj etch\$4) or RIE) and (silicon adj dioxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 8	65	(cantilever and probe and tip) and dop\$3 and ((dry adj etch\$4) or (reactive adj ion adj etch\$4) or RIE) and (silicon adj dioxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 7	682	(cantilever and probe and tip) and "250"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 6	3691	cantilever and probe and tip	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 5	34	cantilever and probe and tip and (silicon adj dioxide) and doped and (dry adj etch\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 4	123	cantilever and probe and tip and (silicon adj dioxide) and doped and mask	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S12 3	66	((silicon same (wafer or substrate)) and probe and cantilever and body and tip and ("p type" or p-type or boron)) and "110"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 2	165	(silicon same (wafer or substrate)) and probe and cantilever and body and tip and ("p type" or p-type or boron)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 1	362302	(silicon same (wafer or substrate)) and probe and cantilever and body and tip and "p type" or p-type or boron	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S12 0	399238	silicon same (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S11 9	126884	silicon adj dioxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S11 8	4	(((((reactive adj ion) or (dry adj etch\$4)) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6"))))) and probe and cantilever and mask and layer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S11 7	1546	(((((reactive adj ion) or (dry adj etch\$4)) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6")))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S11 6	55	"5021364"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S11 5	26	"5489774"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S11 4	15	"5856967"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S11 3	280	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4 or (p adj type) or "p-type" or (p adj doped)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S11 2	26	("4382228" "4480223" "4585991" "4599559" "4719417" "4961052" "5172050" "5177438" "5177439" "5475318" "5521518" "5723347" "5869974" "5900738" "5903161" "5923952" "5926029" "5929498" "5959957" "5965943" "6037785" "6064217" "6072190" "6146917" "6246245" "6279227").PN.	USPAT	OR	OFF	2006/04/11 13:07
S11 1	17	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4 or (p adj type) or "p-type" or (p adj doped))) and ("110" same crystal same substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S11 0	280	probe and cantilever and mask and silicon and (boron or boron-diffus\$4 or (p adj type) or "p-type" or (p adj doped))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 9	5	("4943719" or "4968585" or "5021364" or "5475318" or "5489774" or "5856964") and ((reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6")))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 8	267	"4943719" or "4968585" or "5021364" or "5475318" or "5489774" or "5856964"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 7	47	"4968585"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S10 6	10	((reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6")))) and probe and cantilever	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 5	1	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and ((reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6"))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 4	923	(reactive adj ion) and ((he or helium) and (o2 or "o.sub.2") and ((sulfur adj hexaf\$6) or "SF.sub.6"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 3	9	((((probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and (((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))) and "<110>") and (reactive adj ion)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 2	0	(((((probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and (((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))) and "<110>") and (reactive adj ion)) and He	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 1	28	((probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and (((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))) and "<110>"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S10 0	38	(probe and cantilever and mask and silicon and (boron or boron-diffus\$4)) and (((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S99	120	((probe same cantilever) and ("SiO.sub.2")) and ((probe same cantilever) and (silicon adj dioxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S98	328	(probe same cantilever) and (silicon adj dioxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S97	387	(probe same cantilever) and ("SiO.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S96	4858	probe same cantilever	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S95	1	09/598656	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S94	1	09/598,656	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S93	49018	cho.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S92	205	probe and cantilever and mask and silicon and (boron or boron-diffus\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S91	9	Il-Joo.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S90	2270	choo.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S89	0	Il-Choo	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07

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S88	5	"5856964"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S87	26	"5489774"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S86	122	"5475318"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S85	55	"5021364"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S84	44	"4943719"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/11 13:07
S16 4	18	(boron and silicon and "<110>" and etch\$4 and photoresist).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 13:24
		(boron and silicon and "<110"> and etch\$4 and photoresist).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 13:24
L1	2008	216/2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 14:38
L2	3211	250/306	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 14:51
L4	38	(silicon and substrate and boron and diffus\$4 and mask and anisotropic).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 14:54

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L6	0	(photoresist and cantilever and silicon and substrate and boron and diffus\$4 and mask and anisotropic).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 14:55
L5	11	(photoresist and silicon and substrate and boron and diffus\$4 and mask and anisotropic).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 14:55
L3	0	(probe and silicon and substrate and boron and diffus\$4 and mask and anisotropic).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/11 14:55